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Santa Clara, CA – SPIE published two technical papers by Multibeam Corporation in the 2011 Proceedings of the Advanced Lithography Symposium. These papers follow a series of presentations on E-Beam Lithography (EBL) in the United States and Japan, by Multibeam.

The first paper, titled “E-Beam to Complement Optical Lithography for 1D Layouts” introduces the concept of Complementary Electron-Beam Lithography (CEBL).

In high-volume manufacturing, Multibeam’s EBL patterns only layers with the smallest features with high-resolution electron beams, while all other layers are patterned with existing Optical Lithography. This is known as CEBL. By compensating for the performance of Optical Lithography, CEBL enables the most cost-efficient production of next-generation microchips.

The second paper, titled “Optimization of E-beam Landing Energy”, includes simulations and analyses of the tradeoffs of various e-beam landing energies. Multibeam reported an optimal process window for CEBL, in terms of patterning resolution and overlay accuracy, with e-beam landing energy ranging from 10 keV to 15 keV.

About the 2011 SPIE Advanced Lithography Symposium

The SPIE Advanced Lithography Symposium is the premier annual international forum bringing practitioners of micro- and nanolithography together in a stimulating, informative, and interactive environment. The 2011 Symposium was held in San Jose, CA, from Feb 28 to Mar 4, 2011. More information is available at www.spie.org/advanced-lithography.xml.

About Multibeam Corporation

Multibeam is the technology leader in high-speed multiple-column E-Beam Lithography (EBL). In 2011, Multibeam introduced Complementary EBL (CEBL). CEBL extends Optical Lithography and enables the production of next-generation semiconductors in high volumes at reduced cost. Multibeam is led by Dr. David K. Lam, founder and former CEO of Lam Research Corporation. More information is available at www.multibeamcorp.com.

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